

Chad M Huard

List of Publications by Year in descending order

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9
papers

343
citations

1163117
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1588992
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9
docs citations

9
times ranked

481
citing authors

#	ARTICLE	IF	CITATIONS
1	Plasma etching of high aspect ratio features in SiO ₂ using Ar/C ₄ F ₈ /O ₂ mixtures: A computational investigation. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019, 37, .	2.1	64
2	Highly stable and stretchable graphene-polymer processed silver nanowires hybrid electrodes for flexible displays. <i>Journal of Materials Chemistry C</i> , 2015, 3, 1528-1536.	5.5	56
3	Transient behavior in quasi-atomic layer etching of silicon dioxide and silicon nitride in fluorocarbon plasmas. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2018, 36, .	2.1	45
4	Role of neutral transport in aspect ratio dependent plasma etching of three-dimensional features. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017, 35, .	2.1	44
5	Abnormal Multiple Charge Memory States in Exfoliated Few-Layer WSe ₂ Transistors. <i>ACS Nano</i> , 2017, 11, 1091-1102.	14.6	42
6	ITO-free, Compact, Color Liquid Crystal Devices Using Integrated Structural Color Filters and Graphene Electrodes. <i>Advanced Optical Materials</i> , 2014, 2, 435-441.	7.3	40
7	Investigation of feature orientation and consequences of ion tilting during plasma etching with a three-dimensional feature profile simulator. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017, 35, .	2.1	34
8	Consequences of atomic layer etching on wafer scale uniformity in inductively coupled plasmas. <i>Journal Physics D: Applied Physics</i> , 2018, 51, 155201.	2.8	18
9	Origins of aspect ratio dependent etching in plasma materials processing. , 2016, , .		0